



INFORMATION DISCLOSURE CITATION
1. ~~100-3~~ *(Use several sheets if necessary)*

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Filing Date

January 9, 2002

Group Art Unit

1752

U.S. PATENT DOCUMENTS

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FOREIGN PATENT DOCUMENTS

REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						YES	NO
21A	WO 02 093263 A 1	11/21/2002	Europe				

OTHER DOCUMENTS *(Including Author, Title, Date, Pertinent Pages, Etc.)*

RA

- Padmanaban et al, XP-008014024, "Materials and Resists for 193 and 157 nm Applications", Journal of Photopolymer Science and Technology, CHIBA, JP, vol. 14, no. 4, 2001, pages 631-642

EXAMINER

R. Ashton

DATE CONSIDERED

1-10-04

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.